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Evaluation of interfacial toughness of film/substrate by nanoindenter

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Key Words: interfacial toughness(), nanoindenter(), thin film()

Abstract

A method to measure the interfacial toughness of film/substrate by nanoindenter is proposed. As the thickness of the film decreases, the measurement of the interfacial toughness requires the more sophisticated equipment such as nanoindenter. In this study, the nanoindenter is applied to the substrate near the interface of film/substrate in the direction perpendicular to the normal of the interface, causing the cohesive fracture of the substrate, followed by the interfacial cracking. The specimen of Cu(0.56 μ m)/Si(530 μ) are made by sputtering the copper onto the silicon wafer. By scratching the copper surface, we can make the easy interfacial cracking during the nanoindentation. It is found that the averaged values of the interfacial toughness of the Cu/Si is $0.664 \pm 0.3 \text{ J/m}^2$. The phase angle of the specimen in this study is $\psi \simeq -36.8^\circ$, computed by the method of Suo and Hutchinson.[1]

가

1.

/

가

가

tation test()

가

Inden-

Si()

Sanchez [2]

가

가

2. 가

†

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2.1

*

가
 phase angle() ψ
 가
 가
 가
 가
 meter . [3] Dundurs para-
 meter (1), (2)

$$\alpha = \frac{\mu_1(\kappa_2 + 1) - \mu_2(\kappa_1 + 1)}{\mu_1(\kappa_2 + 1) + \mu_2(\kappa_1 + 1)}, \quad (1)$$

$$\beta = \frac{\mu_1(\kappa_2 - 1) - \mu_2(\kappa_1 - 1)}{\mu_1(\kappa_2 + 1) + \mu_2(\kappa_1 + 1)}. \quad (2)$$

μ shear modulus()
 $\kappa = 3 - 4\nu$,
 $\kappa = (3 - \nu)/(1 + \nu)$, ν
 (3) . [1]

$$\begin{aligned} \sigma_{22} + i\sigma_{12}|_{\theta=0} &= \frac{K}{\sqrt{2\pi r}} r^{i\epsilon} \\ &= \frac{|K|}{\sqrt{2\pi r}} e^{i\psi}. \end{aligned} \quad (3)$$

$K(= K_1 + iK_2)$
 $i = \sqrt{-1}$, r crack tip()
 $\theta = 0$
 . bimaterial constant() ϵ
 (4)

$$\epsilon = \frac{1}{2\pi} \ln \left(\frac{1 - \beta}{1 + \beta} \right). \quad (4)$$

Mode mixity()
 ψ (5)

$$\begin{aligned} \psi &= \tan^{-1} \left(\frac{\sigma_{12}}{\sigma_{22}} \Big|_{\theta=0} \right) \\ &= \tan^{-1} \left[\frac{\text{Im}(Kr^{i\epsilon})}{\text{Re}(Kr^{i\epsilon})} \right] \\ &= \tan^{-1} \left(\frac{K_2}{K_1} \right) + \epsilon \ln r. \end{aligned} \quad (5)$$
 (3)

$r^{i\epsilon}$ 가
 K 가
 $(stress) \times (length)^{1/2 - i\epsilon}$ 가
 Rice[8] characteristic length
 (r) \hat{r} (K_I
 K_{II}) 가
 $(stress) \times (length)^{1/2}$ 가
 가
 가 (load phase)
 (phase angle) 가

(5) $\epsilon = 0$
 $\epsilon \ln r$, 0(
)

2.2
 Fig. 1
 F 가

가 a

deflection() Δ
 a F
 가

Fig. 1 cantilever slab()

가 F , Δ
 , free edge()
 Δ (6) .[5]

$$\Delta = K_y \frac{F a^2}{\pi D} \quad (6)$$

$D = E h^3 / 12 (1 - \nu^2)$
 (flexural rigidity of the plate)

E , h , ν , K_y

, Roark Young[5]

(B/a) c (Fig. 1) (c/a)
 (6)

elastic compliance C

$$C = \frac{\Delta}{F} = \frac{K_y a^2}{\pi D} \quad (7)$$

G ($F = constant$)
 ($\Delta = constant$)

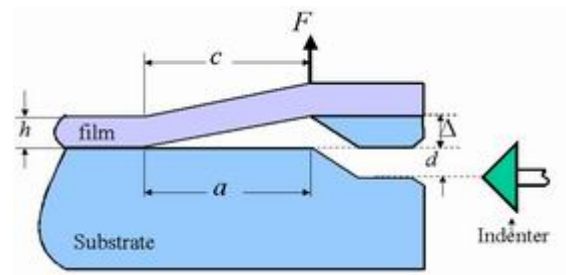


Fig. 1 Cantilever slab model (where h is film thickness, d is distance from interface to indenter tip, a is crack length, Δ is deflection, c is distance from fixed end to point of application, and F is applied force).

$$G = \frac{F}{2B} \left(\frac{d\Delta}{da} \right)_{F=constant} \quad (8)$$

$$= \frac{F^2}{2B} \frac{dC}{da} = K_y \frac{F^2 a}{\pi B D}$$

B
 Obreimoff[6]

F a 가
 (6) $F = \pi D \Delta / K_y a^2$

G (8) F
 (9)

$$G = \frac{\pi}{K_y} \frac{D \Delta^2}{B a^3} \quad (9)$$

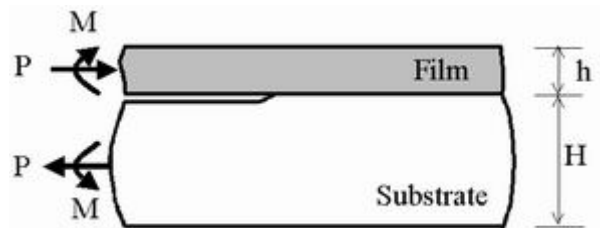


Fig. 2 Infinite double strip model

2.3

, Suo Hutchinson[1]

Fig. 2

h ,

H

$P = 0$

$M (= Fa)$

가

Cu(0.56 μm)/Si(530

μm)

4

$\alpha = 0.036$, $\beta = -0.016$

\hat{r}

h

Suo

Hutchinson[1]

, Cu/Si

$\psi = -36.8^\circ$

3.

3.1

BAL-TEC Sputter Coater

, 4 P-100 type Si (500 550

3.2

μm), 0.56 μm Cu

가 Fig. 3

가

line, cleavage vise가

puck

MTS Nano Indenter[®] XP(50 nN, 0.01 nm)

, load-depth sensing technique

가

slab)

(cantilever

Berkovich

3.3

Fig. 3

50 nm

(9)

a

Δ

Fig. 4 SEM(

a_L

a_R

$(a_L + a_R)/2$

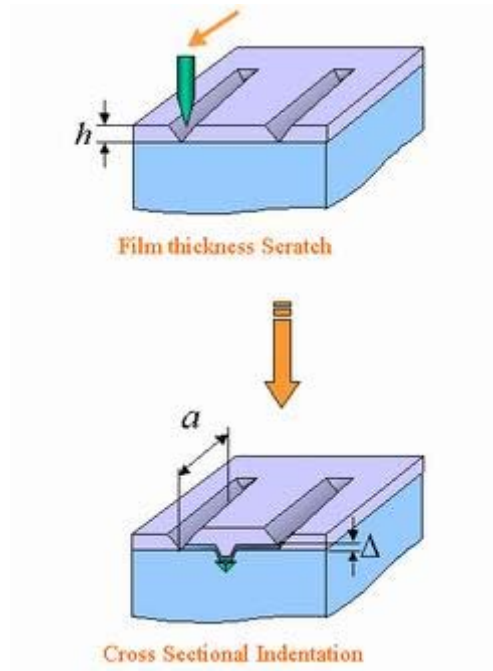
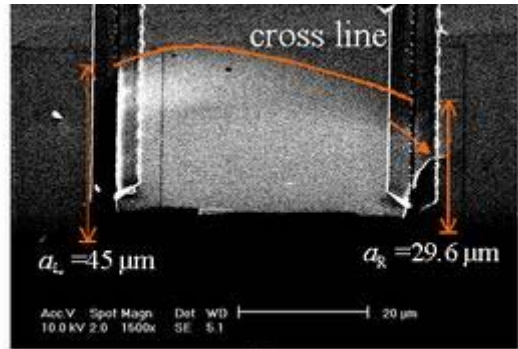
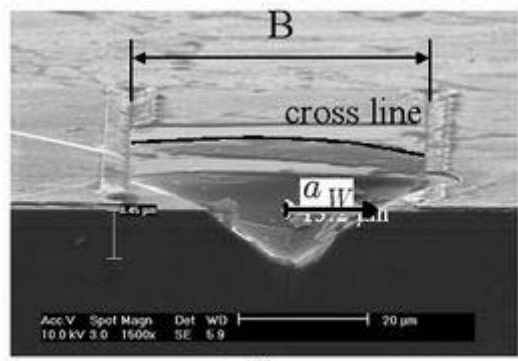


Fig. 3 Scratch and cross-sectional indentation test

a_A
 가
 가
 a_A
 a_W
 $a (= a_A - a_W)$
 Sanchez [2]



(a)



(b)

Fig. 4 SEM photos. (a)measuring interfacial crack length (b)wedge radius a_w

Fig. 5
 가
 가
 (Fig. 5 A B)
 , Si
 가
 Cu/Si
 unloading()

y_D (Fig. 5)
 Δ
 F
 Fig. 5
 y_U
 depth() y_R
 y_D
 $y_U = y_R + y_D$
 residual Δ
 .[2]

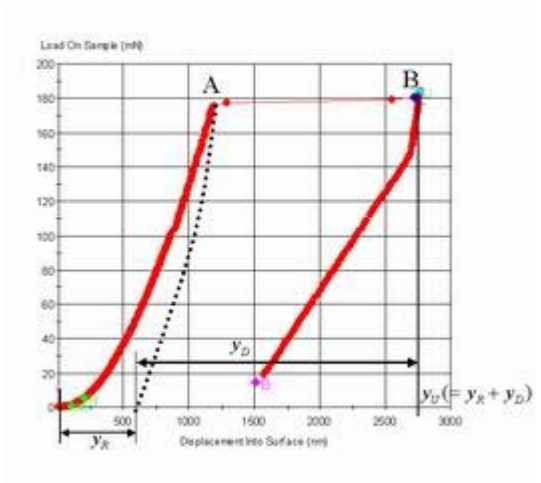


Fig. 5 Load - tip displacement curve (Fracture occurs)

y_R
 loading() 가
 가
 Berkovich Δ y_D
 .[2]
 $\Delta = y_D \times \tan 65.3^\circ$
 (11)

4.

Cu/Si ,
가

$$E_c = 117 GPa, \nu_c = 0.33$$

$$E_s = 130 GPa, \nu_s = 0.28 \quad [7] \quad (1)$$

(2) Dundurs parameter
 $\alpha = 0.036, \beta = -0.016, \quad (4)$
 bimaterial constant $\epsilon = 0.005$

Table 1

a , Δ
 G
 0.664 J/m²(
 2.3 0.3),
 $\psi = -36.8^\circ$
 가

Cu/Si

Table 1 Test result

Test	Interfacial crack length $a (\mu m)$	Deflection of film $\Delta (\mu m)$	Critical energy release rate $G (J/m^2)$
1	25.1	4.76	0.46
2	24.1	6.82	1.00
3	28.2	4.78	0.66
4	21.3	4.46	0.86
5	24.9	5.85	1.01
6	31.0	4.00	0.34
7	45.4	6.11	0.32

가 CARE(Computer Aided Reliability Evaluation)

- (1) Suo, Z. and Hutchinson, J.W. (1990), "Interface crack between two elastic layers," *Int. J. of Fracture* 43, pp. 1-18
- (2) Sanchez, J.M. et al. (1999), "Cross-sectional nanoindentation: A new technique for thin film interfacial adhesion characterization," *Acta Materialia* 47, pp. 4405-4413
- (3) Dundurs, J. (1969), "Edge-bonded dissimilar orthogonal elastic wedges," *J. of Applied Mechanics* 36, pp.650-652
- (4) Rice, J.R. (1988), "Elastic fracture mechanics concepts for interfacial cracks," *J. of Applied Mechanics* 55, pp. 98-103
- (5) Roark, R.J. and Young, W.C. (1975), *Formulas for stress and strain* 5th ed., McGraw-Hill Inc.
- (6) Obreimoff, J.W. (1930), "The splitting strength of mica," *Proceeding of The Royal Society Ser.A* 127, pp.290-297
- (7) Bhushan, B. (1999), *Handbook of micro/nanotribology* 2nd ed., CRC Press